

Title (en)

METHOD OF MANUFACTURING A SEMICONDUCTOR DEVICE WITH AN ISOLATION REGION AND A DEVICE MANUFACTURED BY THE METHOD

Title (de)

VERFAHREN ZUR HERSTELLUNG EINER HALBLEITERVORRICHTUNG MIT EINEM ISOLATIONSBEREICH UND MIT DIESEM VERFAHREN HERGESTELLTE HALBLEITERVORRICHTUNG

Title (fr)

PROCEDE DE FABRICATION D'UN DISPOSITIF A SEMI-CONDUCTEUR PRESENTANT UNE REGION D'ISOLATION ET DISPOSITIF FABRIQUE SELON LE PROCEDE

Publication

**EP 1927133 A2 20080604 (EN)**

Application

**EP 06795914 A 20060905**

Priority

- IB 2006053118 W 20060905
- EP 05108164 A 20050906
- EP 06795914 A 20060905

Abstract (en)

[origin: WO2007029178A2] A method of manufacturing a semiconductor device includes forming trench isolation structures, exposing some of the trench isolation structures 28 to leave others 30 masked, and then selectively etching a buried layer to form a cavity 32 under an active device region 34. The active device region 34 is supported by support regions in the exposed trenches 28. The buried layer may be a SiGe layer on a Si substrate.

IPC 8 full level

**H01L 21/762** (2006.01)

CPC (source: EP US)

**H01L 21/762** (2013.01 - US); **H01L 21/76224** (2013.01 - US); **H01L 21/76264** (2013.01 - EP US); **H01L 21/76283** (2013.01 - US); **H01L 27/1207** (2013.01 - US); **H01L 29/0649** (2013.01 - US); **H01L 29/267** (2013.01 - US)

Citation (search report)

See references of WO 2007029178A2

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